We claim:

1. A stripping composition consisting essentially of

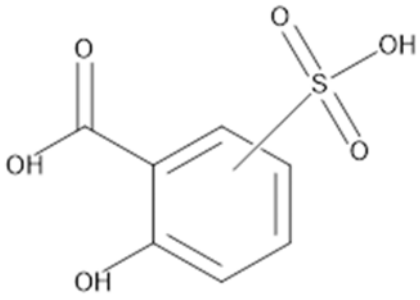
one of at least one sulfosalicylic acids having structure (I), its hydrate, or a mixture of this sulfosalicylic acid and its hydrate;

a primary solvent selected from acetone, and methyl ethyl ketone, or a mixture of these solvents,

a secondary solvent which is a glycolic derivative, or a mixture of at least two glycolic derivatives, wherein said secondary solvent is selected from the group consisting of alkylenediols, oligo(alkyleneoxyalkylene) diols [HO-(alkylene-O-alkylene-O)n-H] (n= 1 to 4), monoalkyl ethers of alkylenediols, monoalkyl ethers of oligo(alkyleneoxyalkylene) diols, dialkyl ethers of alkylenediols, dialkyl ethers of oligo(alkyleneoxyalkylene) diols, alkylenediols in which one of the hydroxy groups is functionalized as an alkylcarboxylate and the other is functionalized as an ether, oligo(alkyleneoxyalkylene) diols in which one of the hydroxy groups is functionalized as an alkylcarboxylate and the other is functionalized as an ether, alkylenediols in which one of the hydroxy groups is functionalized as an alkylcarboxylate, oligo(alkyleneoxyalkylene) diols in which one of the hydroxy groups is functionalized as an alkylcarboxylate, alkylenediols in which both of the hydroxy groups are functionalized as alkylcarboxylates and oligo(alkyleneoxyalkylene) diols in which both of the hydroxy groups is functionalized as alkylcarboxylates;

and an optional surfactant,

wherein these constituents form at least 90 wt% of the composition;



(I).

2. The composition of claim 1 consisting of

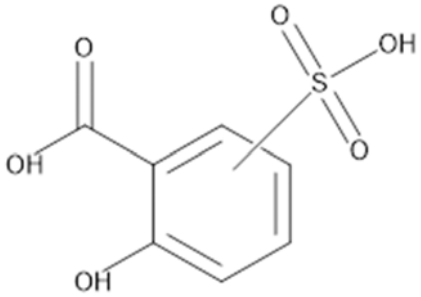
one of at least one sulfosalicylic acids having structure (I), its hydrate, or a mixture of this sulfosalicylic acid and its

hydrate;

a primary solvent selected from acetone, and methyl ethyl ketone, or a mixture of these solvents,

a secondary solvent which is a glycolic derivative, or a mixture of at least two glycolic derivatives, and

an optional surfactant;



(I).

~~3. The composition of claim 1, consisting essentially of~~

~~one of at least one sulfosalicylic acid having structure (I), its hydrate, or a mixture of this sulfosalicylic acid and its hydrate;~~

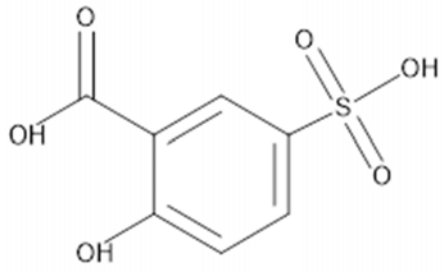
~~a primary solvent selected from acetone, and methyl ethyl ketone, or a mixture of these solvents; and a secondary solvent which is a glycolic derivative, or a mixture of at least two glycolic derivatives.~~

~~4. The composition of any one of claims 1 to 3, consisting of~~
~~one of at least one sulfosalicylic acid having structure (I), its hydrate, or a mixture of this sulfosalicylic acid and its hydrate;~~
~~a primary solvent selected from acetone, and methyl ethyl ketone, or a mixture of these solvents; and a secondary solvent which is a glycolic derivative, or a mixture of at least two glycolic derivatives.~~

~~5. The composition of claim 1 consisting essentially of~~
~~one of at least one sulfosalicylic acid having structure (I), its hydrate, or a mixture of this sulfosalicylic acid and its hydrate,~~
~~a primary solvent selected from acetone, and methyl ethyl ketone, or a mixture of these solvents, and a secondary solvent which is a glycolic derivative, or a mixture of at least two glycolic derivatives, and a surfactant.~~

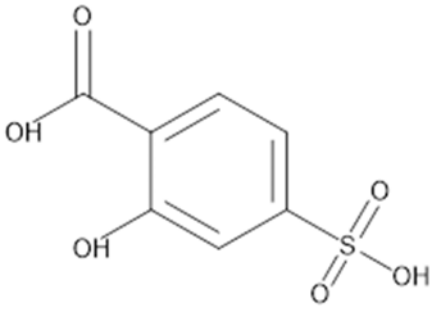
~~6. The composition of claims 1 or 2 consisting of one of at least one sulfosalicylic acid having structure (I), its hydrate, or a mixture of this sulfosalicylic acid and its hydrate,~~
~~a primary solvent selected from acetone, and methyl ethyl ketone, or a mixture of these solvents, and a secondary solvent which is a glycolic derivative, or a mixture of at least two glycolic derivatives, and a surfactant.~~

~~7~~3. The composition of ~~any one of~~ claim~~s~~ 1 ~~to 6~~ or 2, wherein said sulfosalicylic acid is one having structure (Ia) or its hydrate:



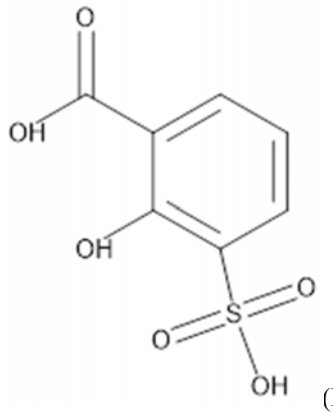
(Ia).

~~8~~4. The composition of ~~any one of~~ claim~~s~~ 1 ~~to 6~~ or 2, wherein said sulfosalicylic acid is one having structure (Ib) or its hydrate:



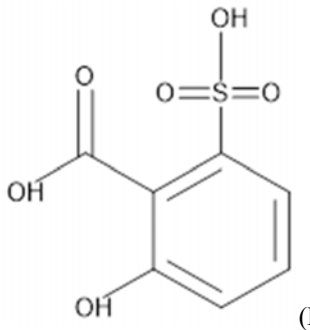
(Ib),

~~9~~5. The composition of ~~any one of~~ claims ~~1 to 6~~ or 2, wherein said sulfosalicylic acid is one having structure (Ic) or its hydrate:



(Ic).

~~10~~6. The composition of ~~any one of~~ claims ~~1 to 6~~ or 2, wherein said sulfosalicylic acid is one having structure (Id) or its hydrate:



(Id).

~~11~~7. The composition of any one of claims 1 to ~~10~~ 6, wherein said primary solvent is acetone or methyl ethyl ketone.

~~12. The composition of any one of claims 1 to 11, wherein said primary solvent is methyl ethyl ketone.~~

~~13~~8. The composition of any one of claims 1 to ~~12~~ 6, wherein said primary solvent is a mixture of acetone

and methyl ethyl ketone.

~~14. The composition of any one of claims 1 to 13, wherein said secondary solvent is selected from the group consisting alkylenediols, oligo(alkyleneoxyalkylene) diols [HO (alkylene-O-alkylene-O)n-H] (n= 1 to 4), monoalkyl ethers of alkylenediols, monoalkyl ethers of oligo(alkyleneoxyalkylene) diols, dialkyl ethers of alkylenediols, dialkyl ethers of oligo(alkyleneoxyalkylene) diols, alkylenediols in which one of the hydroxy groups is functionalized as an alkylcarboxylate and the other is functionalized as an ether, oligo(alkyleneoxyalkylene) diols in which one of the hydroxy groups is functionalized as an alkylcarboxylate and the other is functionalized as an ether, alkylenediols in which one of the hydroxy groups is functionalized as an alkylcarboxylate, oligo(alkyleneoxyalkylene) diols in which one of the hydroxy groups is functionalized as an alkylcarboxylate, alkylenediols in which both of the hydroxy groups are functionalized as alkylcarboxylates, oligo(alkyleneoxyalkylene) diols in which both of the hydroxy groups is functionalized as alkylcarboxylates.~~

~~15. The composition of claim 14, wherein said secondary solvent is an alkanediol.~~

~~16. The composition of claim 14, wherein said secondary solvent is an oligo(alkyleneoxyalkylene) diols [HO (alkylene-O-alkylene-O)n-H] (n= 1 to 4).~~

~~17. The composition of claim 14, wherein said secondary solvent is a monoalkyl ether of an alkanediol.~~

~~18. The composition of claim 14, wherein said secondary solvent is a monoalkyl ether of an oligo(alkyleneoxyalkylene) diols [HO (alkylene-O-alkylene-O)n-H] (n= 1 to 4),~~

~~19. The composition of claim 18, wherein said secondary solvent is a dialkyl ether of an alkanediol.~~

~~20. The composition of claim 18, wherein said secondary solvent is a dialkyl ether of an oligo(alkyleneoxyalkylene) diols [HO (alkylene-O-alkylene-O)n-H] (n= 1 to 4).~~

~~21. The composition of claim 14, wherein said secondary solvent is of an alkanediol. in which one hydroxy group is functionalized as an alkyl ether and the other hydroxy group is functionalized as an alkyl carboxylate.~~

~~22. The composition of claim 14, wherein said secondary solvent is an oligo(alkyleneoxyalkylene) diols [HO (alkylene-O-alkylene-O)n-H] (n= 1 to 4) in which one hydroxy is functionalized as an alkyl ether and the other hydroxy is functionalized as an alkylcarboxylate.~~

~~23. The composition of claim 14, wherein said secondary solvent is a an alkylenediol in which one of the hydroxy groups is functionalized as an alkylcarboxylate.~~

~~24. The composition of claim 14, wherein said secondary solvent is an oligo(alkyleneoxyalkylene) diols [HO (alkylene-O-alkylene-O)n-H] (n= 1 to 4) in which one of the hydroxy groups is functionalized as an alkylcarboxylate.~~

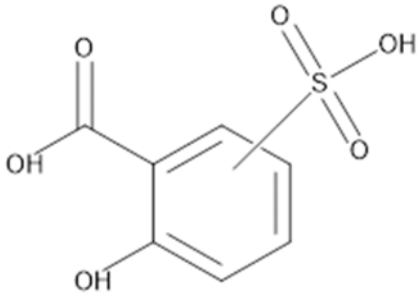
~~25. The composition of claim 14, wherein said secondary solvent is an alkylenediol in which both hydroxy groups are functionalized as an alkylcarboxylates.~~

~~26. The composition of claim 14, wherein said secondary solvent is an oligo(alkyleneoxyalkylene) diols [HO (alkylene-O-alkylene-O)n-H] (n= 1 to 4) in which both hydroxy groups are functionalized as an alkylcarboxylates.~~

~~27~~9. The composition of any one of claims 1 to ~~13~~ 8, wherein said secondary solvent is selected from either a solvent selected from the group consisting of PGME, PGMEA, propylene glycol, dipropylene glycol (IV), dipropylene glycol mono methyl ether (II), dipropylene ~~mono~~ glycol dimethyl ether (III), or a mixture of at least two of these solvents.

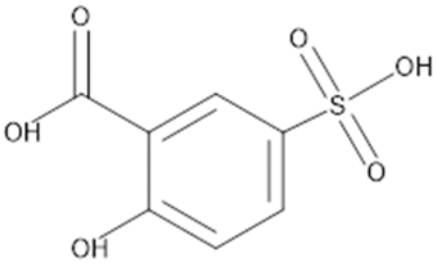
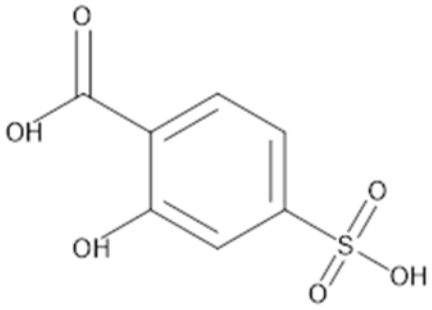
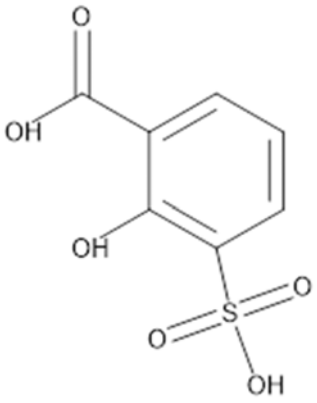
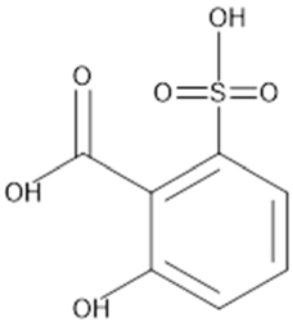
~~28~~10. The composition of claim ~~30~~ 9, wherein said secondary solvent is dipropylene glycol mono methyl ether (II).

~~29~~11. A composition consisting essentially of
one of at least one sulfosalicylic acids having structure (I), its hydrate, or a mixture of this sulfosalicylic acid and its hydrate;
a primary solvent selected from acetone, and methyl ethyl ketone, or a mixture of these solvents,
optionally a secondary solvent which is a glycolic derivative, or a mixture of at least two glycolic derivatives, and optionally a surfactant;



(I),

wherein the sulfosalicylic acid of structure (I) or its hydrate is selected from ones having structures (Ib), (Ic), (Id) or its hydrate, mixtures thereof, and mixtures thereof with ones having structure (Ia) or its hydrate


(Ia),

(Ib),

(Ic),

(Id).

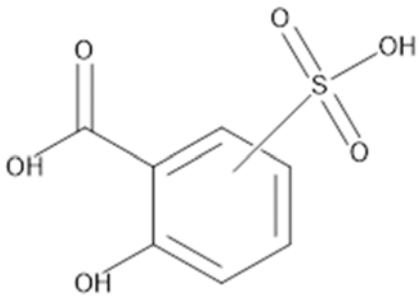
~~30~~12. The composition of claim ~~29~~ 11 consisting of

one of at least one sulfosalicylic acids having structure (I), its hydrate, or a mixture of this sulfosalicylic acid and its hydrate;

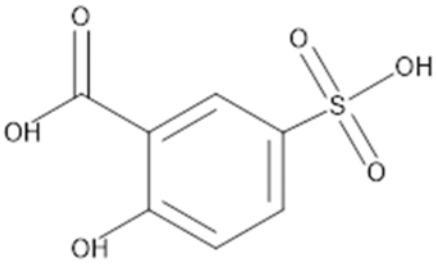
a primary solvent selected from acetone, and methyl ethyl ketone, or a mixture of these solvents,

optionally a secondary solvent which is a glycolic derivative, or a mixture of at least two glycolic derivatives, and

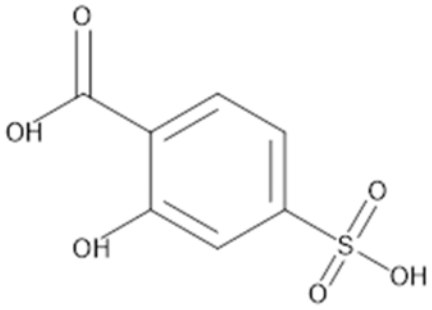
optionally a surfactant;


(I),

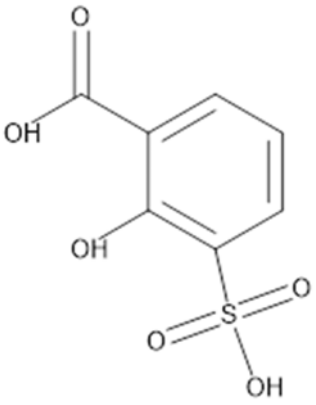
wherein the sulfosalicylic acid of structure (I) or its hydrate is selected from ones having structures (Ib), (Ic), (Id) or its hydrate, mixtures thereof, and mixtures thereof with ones having structure (Ia) or its hydrate



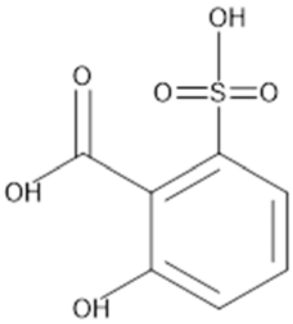
(Ia),



(Ib),



(Ic),



(Id).

~~31~~13. A process comprising the steps:

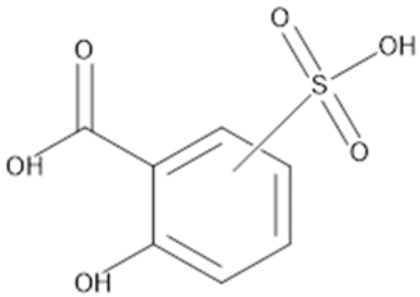
i) thermally adjusting a compositionconsisting essentially of

one of at least one sulfosalicylic acids having structure (I), its hydrate, or a mixture of this sulfosalicylic acid and its hydrate;

a primary solvent selected from acetone, and methyl ethyl ketone, or a mixture of these solvents,

an optional secondary solvent which is a glycolic derivative, or a mixture of at least two glycolic derivatives, and

an optional surfactant;



(I),

to be at a temperature of ~~about~~ 15°C to ~~about~~ 80°C, resulting in a thermally adjusted composition

ii) treating a substrate coated with a photoresist film with said thermally adjusted composition for a time from ~~about~~ 1 minutes to ~~about~~ 60 minutes, until a substrate with a removed photoresist film, results,

iii) after step ii), rinsing said substrate with a removed photoresist film with one of isopropyl alcohol, a mixture of isopropyl alcohol and water, or water to remove any residual composition from step ii), producing a clean substrate,

iv) drying said clean substrate.

~~32~~14. The process of claim ~~31~~ 13, wherein the composition is the composition according to any one of claims 1 to ~~30~~ 12.

~~33. The process of claim 31 or 32, wherein in step i) the composition is thermally adjusted to be about 20°C to about 60°C.~~

~~34. The process of claim 31 or 32, wherein in step i) the composition is thermally adjusted to be about 20°C to about 40°C.~~

~~35. The process of any one of claims 31 to 34, wherein in step ii), the substrate is a metal.~~

~~36. The process of any one of claims 31 to 35, wherein in step ii), the substrate is copper.~~

~~37. The process of any one of claims 31 to 36, wherein in step ii), the substrate is tin.~~

~~38. The process of any one of claims 31 to 37, wherein in step ii), the substrate is silver.~~

~~39. The process of any one of claims 31 to 38, wherein in step ii), the substrate is treated for about 1 minutes to about 20 minutes.~~

~~40. The process of any one of claims 31 to 39, wherein in step iii) the rinse is performed with a mixture of water and isopropanol which has a composition of water ranging from about 5 wt% to about 95 wt%.~~

~~41~~15. The use of the composition of any one of claims 1 to ~~30~~ 12 or as defined in claim ~~31~~ 13 for removing a photoresist film from a substrate.